L Number	Hits	Search Text	DB	Time stamp
7	14031	(photoresist or photosensitive) and (mask$4 or print$4 or record$4) and ((circul$6 or rotat$5) same (stage$1 or table$1 or subtrate$1 or wafer$1 or objet$1))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/29 09:05
8	2507	((photoresist or photosensitive) and (mask$4 or print$4 or record$4) and ((circul$6 or rotat$5) same (stage$1 or table$1 or subtrate$1 or objet$1))) and ((jet$4 or eject$4 or discharg$4) same (mask$4 or print$4 or record$4)) and ((circul$6 or rotat$5) same (stage$1 or table$1 or subtrate$1 or wafer$1 or objet$1))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/29 08:41
9	948	(((photoresist or photosensitive) and (mask$4 or print$4 or record$4) and ((circul$6 or rotat$5) same (stage$1 or table$1 or subtrate$1 or wafer$1 or objet$1))) and ((jet$4 or eject$4 or discharg$4) same (mask$4 or print$4 or record$4)) and ((circul$6 or rotat$5) same (stage$1 or table$1 or subtrate$1 or wafer$1 or objet$1))) and ((jet$4 or eject$4 or discharg$4) same (mask$4 or print$4 or record$4) same (photosensitive or photoresist))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/29 08:41
10	503	((((photoresist or photosensitive) and (mask$4 or print$4 or record$4) and ((circul$6 or rotat$5) same (stage$1 or table$1 or subtrate$1 or wafer$1 or objet$1))) and ((jet$4 or eject$4 or discharg$4) same (mask$4 or print$4 or record$4)) and ((circul$6 or rotat$5) same (stage$1 or table$1 or subtrate$1 or wafer$1 or objet$1))) and ((jet$4 or eject$4 or discharg$4) same (mask$4 or print$4 or record$4) same (photosensitive or photoresist))) and ((circul$6 or rotat$5) with (stage$1 or table$1 or subtrate$1 or wafer$1 or objet$1))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/29 08:41
11	77	(((((photoresist or photosensitive) and (mask$4 or print$4 or record$4) and ((circul$6 or rotat$5) same (stage$1 or table$1 or subtrate$1 or wafer$1 or objet$1))) and ((jet$4 or eject$4 or discharg$4) same (mask$4 or print$4 or record$4)) and ((circul$6 or rotat$5) same (stage$1 or table$1 or subtrate$1 or wafer$1 or objet$1))) and ((jet$4 or eject$4 or discharg$4) same (mask$4 or print$4 or record$4) same (photosensitive or photoresist))) and ((circul$6 or rotat$5) with (stage$1 or table$1 or subtrate$1 or wafer$1 or objet$1))) and 347/$.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/29 08:42
13	48	((((((photoresist or photosensitive) and (mask$4 or print$4 or record$4) and ((circul$6 or rotat$5) same (stage$1 or table$1 or subtrate$1 or wafer$1 or objet$1))) and ((jet$4 or eject$4 or discharg$4) same (mask$4 or print$4 or record$4)) and ((circul$6 or rotat$5) same (stage$1 or table$1 or subtrate$1 or wafer$1 or objet$1))) and ((jet$4 or eject$4 or discharg$4) same (mask$4 or print$4 or record$4) same (photosensitive or photoresist))) and ((circul$6 or rotat$5) with (stage$1 or table$1 or subtrate$1 or wafer$1 or objet$1))) and 347/$.ccls.) and align$4	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/29 08:44

14	35	(((((((photoresist or photosensitive) and (mask$4 or print$4 or record$4) and ((circul$6 or rotat$5) same (stage$1 or table$1 or subtrate$1 or wafer$1 or objet$1))) and ((jet$4 or eject$4 or discharg$4) same (mask$4 or print$4 or record$4)) and ((circul$6 or rotat$5) same (stage$1 or table$1 or subtrate$1 or wafer$1 or objet$1))) and ((jet$4 or eject$4 or discharg$4) same (mask$4 or print$4 or record$4) same (photosensitive or photoresist))) and ((circul$6 or rotat$5) with (stage$1 or table$1 or subtrate$1 or wafer$1 or objet$1))) and 347/$.ccls.) and align$4) and pattern$1	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/29 08:44
15	18	((((((((photoresist or photosensitive) and (mask$4 or print$4 or record$4) and ((circul$6 or rotat$5) same (stage$1 or table$1 or subtrate$1 or wafer$1 or objet$1))) and ((jet$4 or eject$4 or discharg$4) same (mask$4 or print$4 or record$4)) and ((circul$6 or rotat$5) same (stage$1 or table$1 or subtrate$1 or wafer$1 or objet$1))) and ((jet$4 or eject$4 or discharg$4) same (mask$4 or print$4 or record$4) same (photosensitive or photoresist))) and ((circul$6 or rotat$5) with (stage$1 or table$1 or subtrate$1 or wafer$1 or objet$1))) and 347/$.ccls.) and align$4) and pattern$1) and (mask$4 with pattern$1)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/29 08:48
16	17	((((((((photoresist or photosensitive) and (mask$4 or print$4 or record$4) and ((circul$6 or rotat$5) same (stage$1 or table$1 or subtrate$1 or wafer$1 or objet$1))) and ((jet$4 or eject$4 or discharg$4) same (mask$4 or print$4 or record$4)) and ((circul$6 or rotat$5) same (stage$1 or table$1 or subtrate$1 or wafer$1 or objet$1))) and ((jet$4 or eject$4 or discharg$4) same (mask$4 or print$4 or record$4) same (photosensitive or photoresist))) and ((circul$6 or rotat$5) with (stage$1 or table$1 or subtrate$1 or wafer$1 or objet$1))) and 347/$.ccls.) and align$4) and pattern$1) not (((((((((photoresist or photosensitive) and (mask$4 or print$4 or record$4) and ((circul$6 or rotat$5) same (stage$1 or table$1 or subtrate$1 or wafer$1 or objet$1))) and ((jet$4 or eject$4 or discharg$4) same (mask$4 or print$4 or record$4)) and ((circul$6 or rotat$5) same (stage$1 or table$1 or subtrate$1 or wafer$1 or objet$1))) and ((jet$4 or eject$4 or discharg$4) same (mask$4 or print$4 or record$4) same (photosensitive or photoresist))) and ((circul$6 or rotat$5) with (stage$1 or table$1 or subtrate$1 or wafer$1 or objet$1))) and 347/$.ccls.) and align$4) and pattern$1) and (mask$4 with pattern$1))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/29 08:50

| 17 | 29 | (((((photoresist or photosensitive) and (mask$4 or print$4 or record$4) and ((circul$6 or rotat$5) same (stage$1 or table$1 or subtrate$1 or wafer$1 or objet$1))) and ((jet$4 or eject$4 or discharg$4) same (mask$4 or print$4 or record$4)) and ((circul$6 or rotat$5) same (stage$1 or table$1 or subtrate$1 or wafer$1 or objet$1))) and ((jet$4 or eject$4 or discharg$4) same (mask$4 or print$4 or record$4) same (photosensitive or photoresist))) and ((circul$6 or rotat$5) with (stage$1 or table$1 or subtrate$1 or wafer$1 or objet$1))) and 347/$.ccls.) not ((((((photoresist or photosensitive) and (mask$4 or print$4 or record$4) and ((circul$6 or rotat$5) same (stage$1 or table$1 or subtrate$1 or wafer$1 or objet$1))) and ((jet$4 or eject$4 or discharg$4) same (mask$4 or print$4 or record$4)) and ((circul$6 or rotat$5) same (stage$1 or table$1 or subtrate$1 or wafer$1 or objet$1))) and ((jet$4 or eject$4 or discharg$4) same (mask$4 or print$4 or record$4) same (photosensitive or photoresist))) and ((circul$6 or rotat$5) with (stage$1 or table$1 or subtrate$1 or wafer$1 or objet$1))) and 347/$.ccls.) and align$4) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2004/10/29 09:03 |
| 19 | 426 | ((((((photoresist or photosensitive) and (mask$4 or print$4 or record$4) and ((circul$6 or rotat$5) same (stage$1 or table$1 or subtrate$1 or wafer$1 or objet$1))) and ((jet$4 or eject$4 or discharg$4) same (mask$4 or print$4 or record$4)) and ((circul$6 or rotat$5) same (stage$1 or table$1 or subtrate$1 or wafer$1 or objet$1))) and ((jet$4 or eject$4 or discharg$4) same (mask$4 or print$4 or record$4) same (photosensitive or photoresist))) and ((circul$6 or rotat$5) with (stage$1 or table$1 or subtrate$1 or wafer$1 or objet$1))) not ((((((photoresist or photosensitive) and (mask$4 or print$4 or record$4) and ((circul$6 or rotat$5) same (stage$1 or table$1 or subtrate$1 or wafer$1 or objet$1))) and ((jet$4 or eject$4 or discharg$4) same (mask$4 or print$4 or record$4)) and ((circul$6 or rotat$5) same (stage$1 or table$1 or subtrate$1 or wafer$1 or objet$1))) and ((jet$4 or eject$4 or discharg$4) same (mask$4 or print$4 or record$4) same (photosensitive or photoresist))) and ((circul$6 or rotat$5) with (stage$1 or table$1 or subtrate$1 or wafer$1 or objet$1))) and 347/$.ccls.) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2004/10/29 09:03 |

| 20 | 115 | (((((((photoresist or photosensitive) and (mask$4 or print$4 or record$4) and ((circul$6 or rotat$5) same (stage$1 or table$1 or subtrate$1 or wafer$1 or objet$1))) and ((jet$4 or eject$4 or discharg$4) same (mask$4 or print$4 or record$4)) and ((circul$6 or rotat$5) same (stage$1 or table$1 or subtrate$1 or wafer$1 or objet$1))) and ((jet$4 or eject$4 or discharg$4) same (mask$4 or print$4 or record$4) same (photosensitive or photoresist))) and ((circul$6 or rotat$5) with (stage$1 or table$1 or subtrate$1 or wafer$1 or objet$1))) not (((((((photoresist or photosensitive) and (mask$4 or print$4 or record$4) and ((circul$6 or rotat$5) same (stage$1 or table$1 or subtrate$1 or wafer$1 or objet$1))) and ((jet$4 or eject$4 or discharg$4) same (mask$4 or print$4 or record$4)) and ((circul$6 or rotat$5) same (stage$1 or table$1 or subtrate$1 or wafer$1 or objet$1))) and ((jet$4 or eject$4 or discharg$4) same (mask$4 or print$4 or record$4) same (photosensitive or photoresist))) and ((circul$6 or rotat$5) with (stage$1 or table$1 or subtrate$1 or wafer$1 or objet$1))) and 347/$.ccls.)) and ((photoresist or photosensitive) adj layer$1) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2004/10/29 09:11 |

| 21 | 311 | (((((((photoresist or photosensitive) and (mask$4 or print$4 or record$4) and ((circul$6 or rotat$5) same (stage$1 or table$1 or subtrate$1 or wafer$1 or objet$1))) and ((jet$4 or eject$4 or discharg$4) same (mask$4 or print$4 or record$4)) and ((circul$6 or rotat$5) same (stage$1 or table$1 or subtrate$1 or wafer$1 or objet$1))) and ((jet$4 or eject$4 or discharg$4) same (mask$4 or print$4 or record$4) same (photosensitive or photoresist))) and ((circul$6 or rotat$5) with (stage$1 or table$1 or subtrate$1 or wafer$1 or objet$1))) not ((((((photoresist or photosensitive) and (mask$4 or print$4 or record$4) and ((circul$6 or rotat$5) same (stage$1 or table$1 or subtrate$1 or wafer$1 or objet$1))) and ((jet$4 or eject$4 or discharg$4) same (mask$4 or print$4 or record$4)) and ((circul$6 or rotat$5) same (stage$1 or table$1 or subtrate$1 or wafer$1 or objet$1))) and ((jet$4 or eject$4 or discharg$4) same (mask$4 or print$4 or record$4) same (photosensitive or photoresist))) and ((circul$6 or rotat$5) with (stage$1 or table$1 or subtrate$1 or wafer$1 or objet$1))) and 347/$.ccls.)) not ((((((photoresist or photosensitive) and (mask$4 or print$4 or record$4) and ((circul$6 or rotat$5) same (stage$1 or table$1 or subtrate$1 or wafer$1 or objet$1))) and ((jet$4 or eject$4 or discharg$4) same (mask$4 or print$4 or record$4)) and ((circul$6 or rotat$5) same (stage$1 or table$1 or subtrate$1 or wafer$1 or objet$1))) and ((jet$4 or eject$4 or discharg$4) same (mask$4 or print$4 or record$4) same (photosensitive or photoresist))) and ((circul$6 or rotat$5) with (stage$1 or table$1 or subtrate$1 or wafer$1 or objet$1))) not ((((((photoresist or photosensitive) and (mask$4 or print$4 or record$4) and ((circul$6 or rotat$5) same (stage$1 or table$1 or subtrate$1 or wafer$1 or objet$1))) and ((jet$4 or eject$4 or discharg$4) same (mask$4 or print$4 or record$4)) and ((circul$6 or rotat$5) same (stage$1 or table$1 or subtrate$1 or wafer$1 or objet$1))) and ((jet$4 or eject$4 or discharg$4) same (mask$4 or print$4 or record$4) same (photosensitive or photoresist))) and ((circul$6 or rotat$5) with (stage$1 or table$1 or subtrate$1 or wafer$1 or objet$1))) and 347/$.ccls.)) and ((photoresist or photosensitive) adj layer$1)) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2004/10/29 09:15 |

| 22 | 445 | ((((photoresist or photosensitive) and (mask$4 or print$4 or record$4) and ((circul$6 or rotat$5) same (stage$1 or table$1 or subtrate$1 or wafer$1 or objet$1))) and ((jet$4 or eject$4 or discharg$4) same (mask$4 or print$4 or record$4)) and ((circul$6 or rotat$5) same (stage$1 or table$1 or subtrate$1 or wafer$1 or objet$1))) and ((jet$4 or eject$4 or discharg$4) same (mask$4 or print$4 or record$4) same (photosensitive or photoresist))) not (((((photoresist or photosensitive) and (mask$4 or print$4 or record$4) and ((circul$6 or rotat$5) same (stage$1 or table$1 or subtrate$1 or wafer$1 or objet$1))) and ((jet$4 or eject$4 or discharg$4) same (mask$4 or print$4 or record$4)) and ((circul$6 or rotat$5) same (stage$1 or table$1 or subtrate$1 or wafer$1 or objet$1))) and ((jet$4 or eject$4 or discharg$4) same (mask$4 or print$4 or record$4) same (photosensitive or photoresist))) and ((circul$6 or rotat$5) with (stage$1 or table$1 or subtrate$1 or wafer$1 or objet$1))) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2004/10/29 09:16 |